

DPG Frühjahrstagung (SKM),  
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# Thermal conductivity of SiGe-based nanostructures

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# Reduction of the thermal conductivity

- Different approaches through nanostructures like

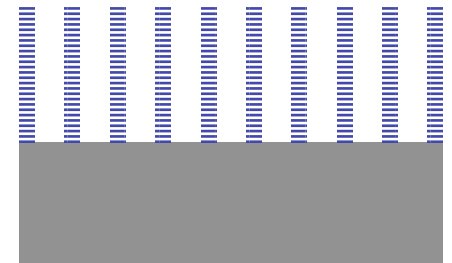
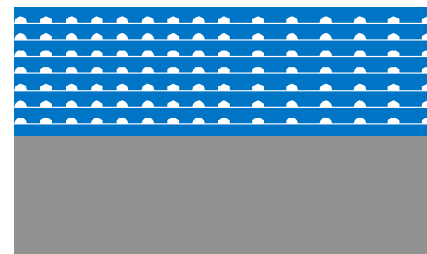
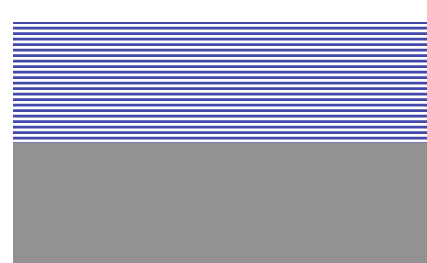
- Superlattices (SL)

- Nanowires (NW)

- Quantum-dot

superlattices (QDSL)

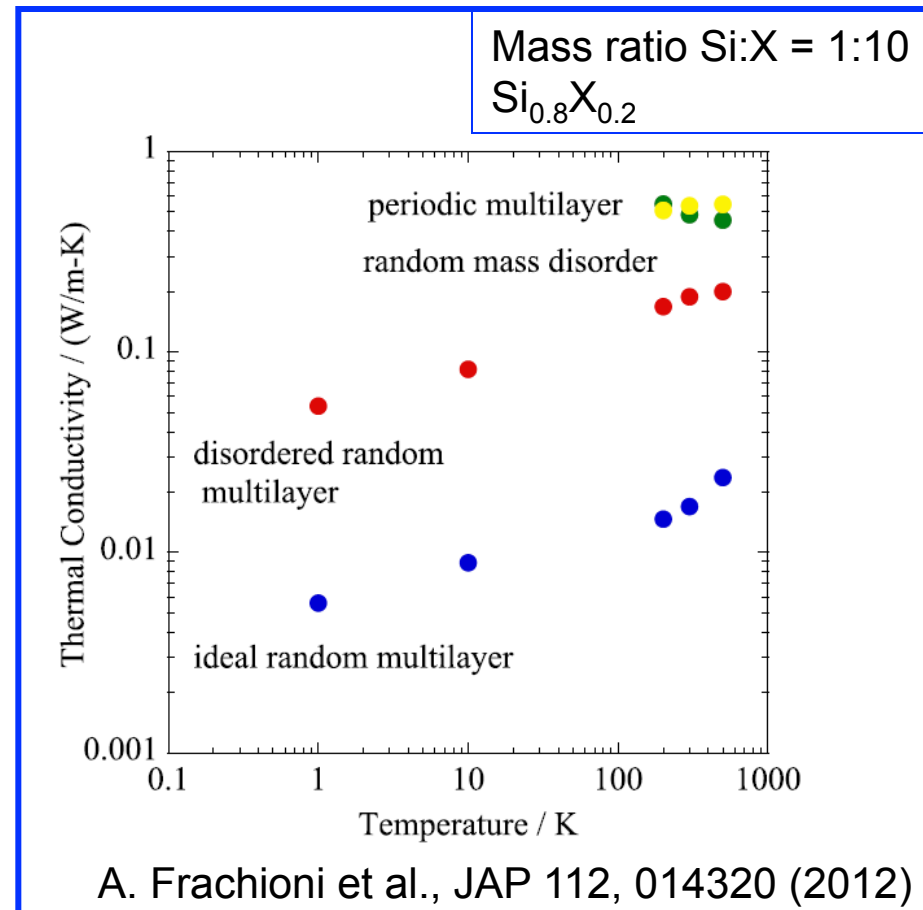
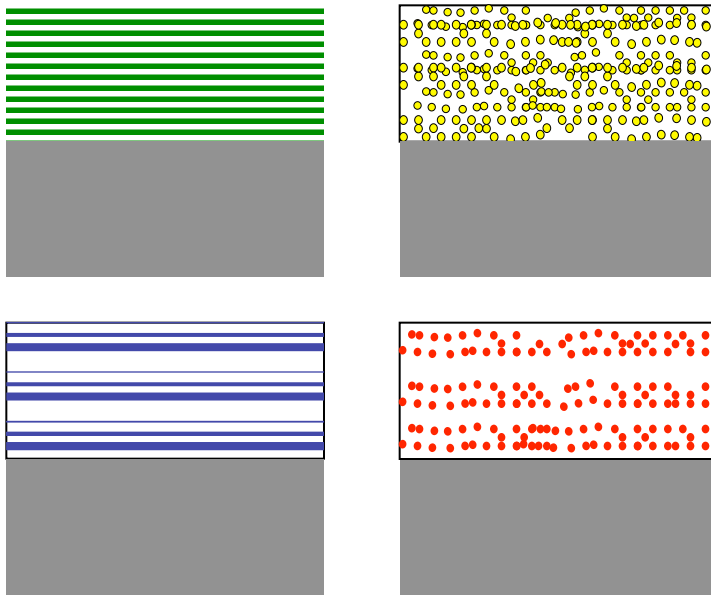
- Nanowires containing  
superlattices (SLNW)



# Reduction of the thermal conductivity

In the case of superlattices a further reduction can be achieved by non-periodic structures

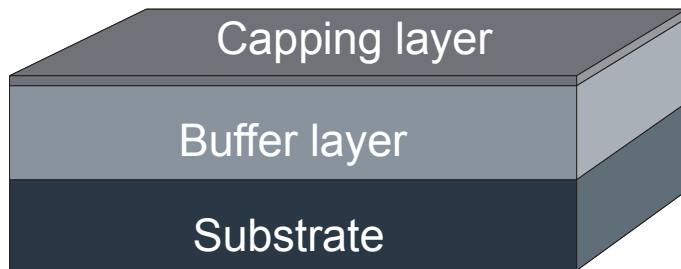
-> localized phonon states



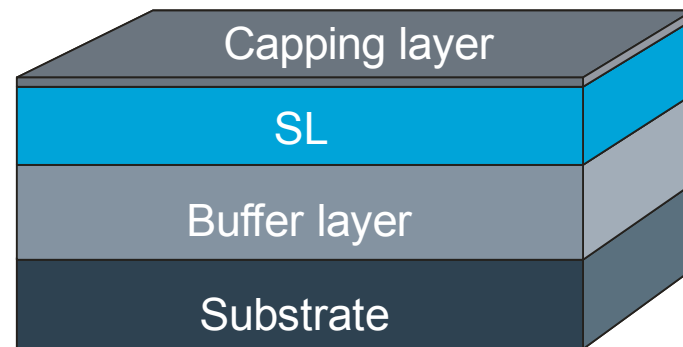
# Sample preparation

Periodic and non-periodic SLs were grown by molecular beam epitaxy (MBE)

- Substrate Temperature  $\sim 550$  K
- Substrate Si (111)
- Si Buffer layer (600 nm)
- Capping layer (10 nm)
- Reference sample without SL



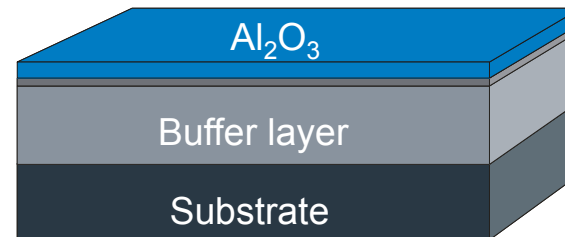
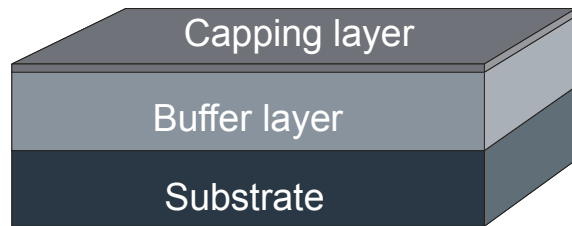
*Reference sample*



*Superlattice sample*

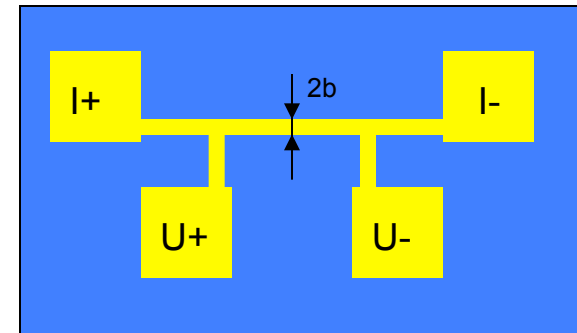
# Measurement setup

- Thermal conductivity was measured by the 3-Omega method
- Electrical insulating layer ->  $\text{Al}_2\text{O}_3$
- Bolometer stripes with different lengths (400  $\mu\text{m}$ , 600  $\mu\text{m}$ , 800  $\mu\text{m}$ ) and widths (3  $\mu\text{m}$ , 5  $\mu\text{m}$ , 6  $\mu\text{m}$ , 8  $\mu\text{m}$ , 10  $\mu\text{m}$ ) were deposited on top



$$V = R_0 I_0 \cos \omega t + \frac{R_0 I_0}{2} \alpha \cdot \Delta T \cos(\omega t + \varphi) + \frac{R_0 I_0}{2} \alpha \cdot \Delta T \cos(3\omega t + \varphi)$$

$$\Delta T = \frac{P_l}{\pi \lambda} \left[ -\frac{1}{2} \ln(2\omega) + \frac{1}{2} \ln \frac{\lambda}{\rho c_p b^2} + \eta \right]$$



# Measurement setup

One-dimensional heat flow:  
Measurement with one  
bolometer stripe ( $2b \gg d_f$ )

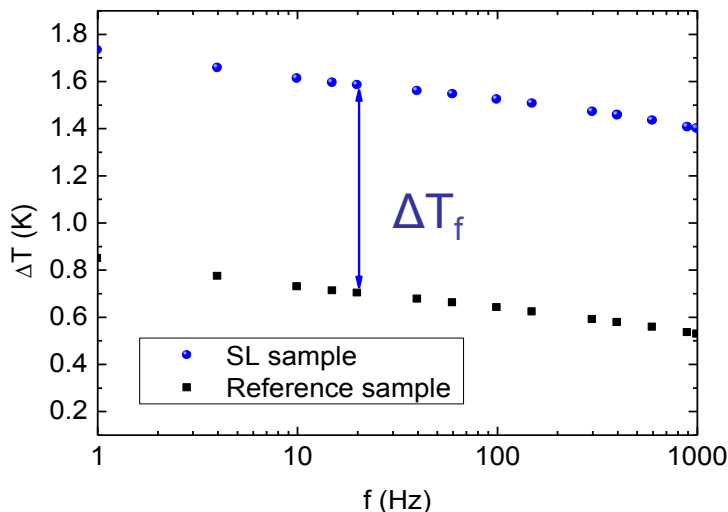
$$\Delta T_f = \frac{P_l d_f}{2b \lambda_{f1D}}$$

Two-dimensional heat flow:  
Measurement with different  
bolometer stripes ( $2b_1, 2b_2$ )

$$\Delta T_f = \frac{P_l d_f}{2b \lambda_{fy}} CS$$

$$C = 1 - \lambda_{fx} \cdot \lambda_{fy} / \lambda_s^2 \quad \beta_f = \sqrt{\lambda_{fx} / \lambda_{fy}} \cdot d_s / b$$

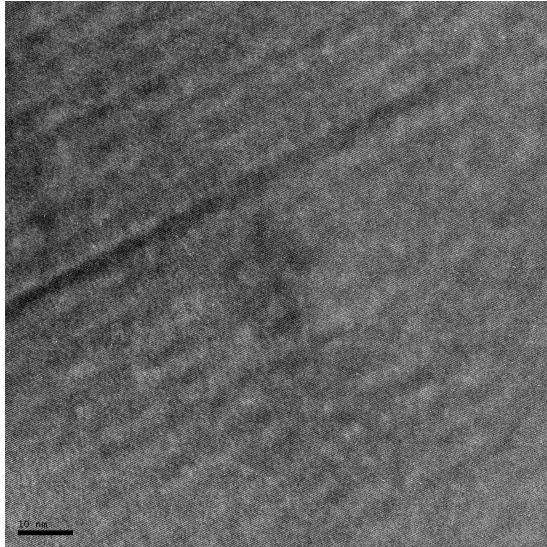
$$S = 2 / \pi \int_0^\infty \frac{\sin^2 \alpha}{\alpha^3} \cdot \frac{\text{Tanh}(\alpha \cdot \beta_f)}{(1 + \sqrt{\lambda_{fy} \cdot \lambda_{fx} / \lambda_s} \cdot \text{Tanh}(\alpha \cdot \beta_f)) \cdot \beta_f} d\alpha$$



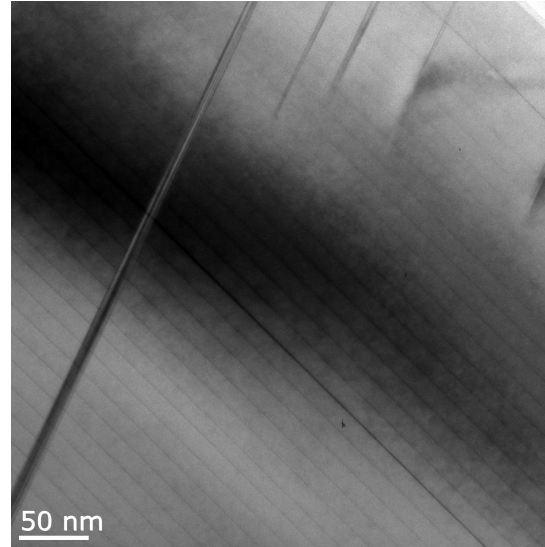
thermal conductivity  
in-plane  $\lambda_{fx}$   
cross-plane  $\lambda_{fy}$



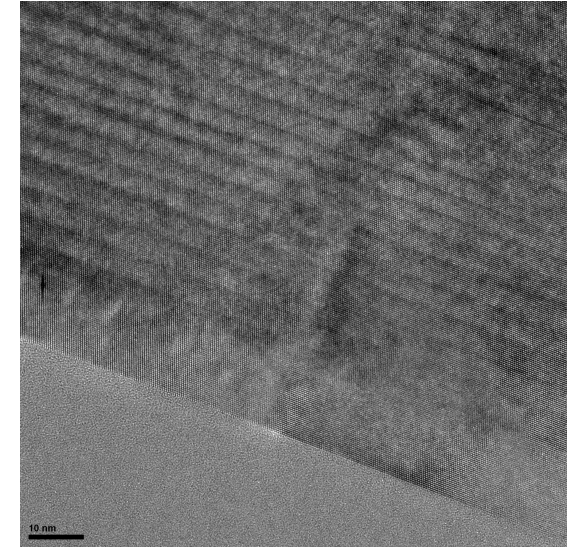
# Samples with periodic layer thickness



111026  
0.2 nm Ge + 3.3 nm Si  
171 times ~ 600 nm



120605  
1.6 nm Ge + 12 nm Si  
39 times ~ 600 nm



101214  
2 nm Ge + 1.5 nm Si  
171 times ~ 600 nm

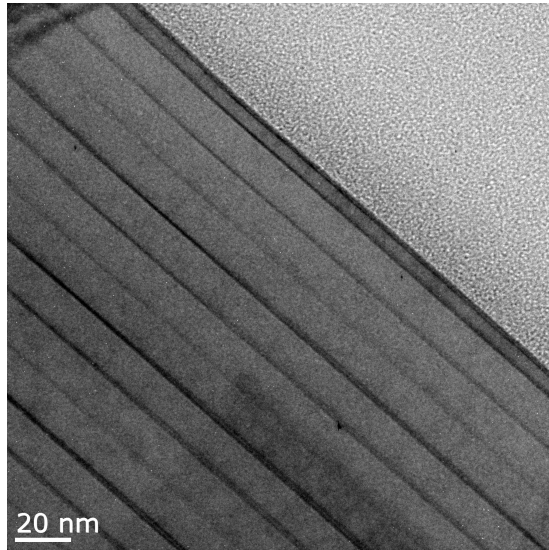
## Ge Content

1.7 %

3.5 %

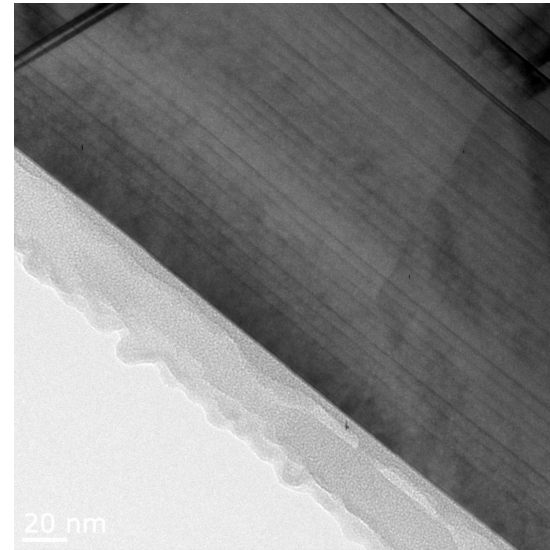
17 %

# Samples with non-periodic layer thickness



## Ge content 2.9 %

1.1 nm Ge + 12 nm Si  
1.2 nm Ge + 12 nm Si  
1.8 nm Ge + 12 nm Si  
1.1 nm Ge + 12 nm Si  
0.9 nm Ge + 12 nm Si  
1.6 nm Ge + 12 nm Si  
6 times ~ 600 nm



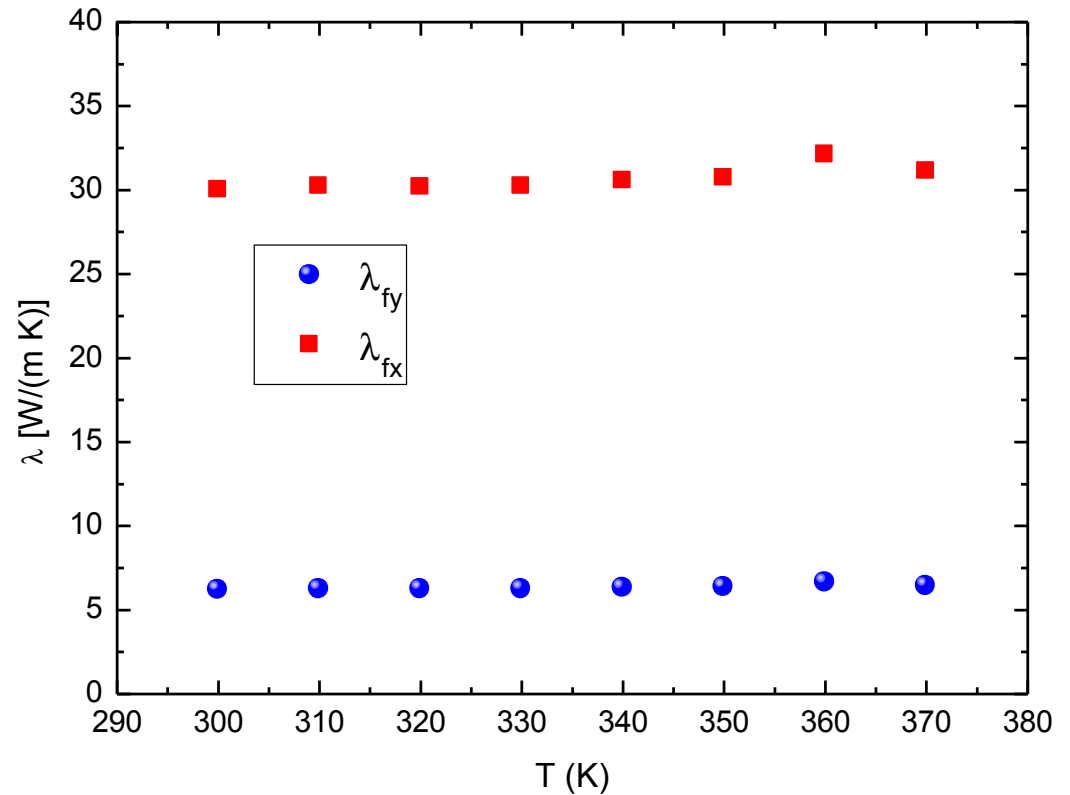
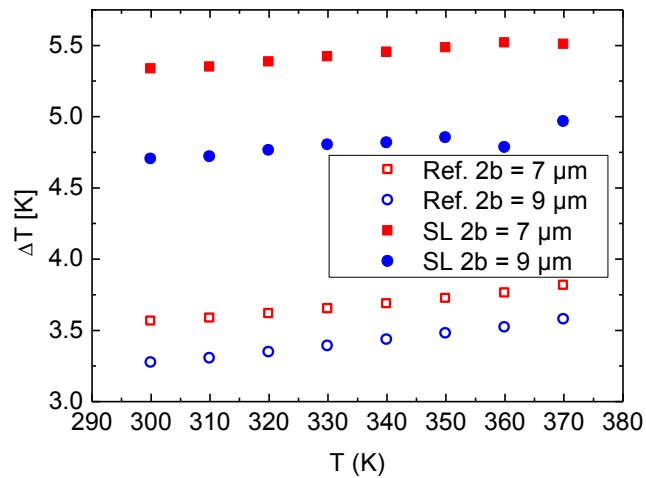
## Ge content 3.3 %

0.6 nm Ge + 4.1 nm Si  
0.3 nm Ge + 5.1 nm Si  
0.8 nm Ge + 4.8 nm Si  
0.6 nm Ge + 5.7 nm Si  
0.6 nm Ge + 3.8 nm Si  
34 times ~ 940 nm



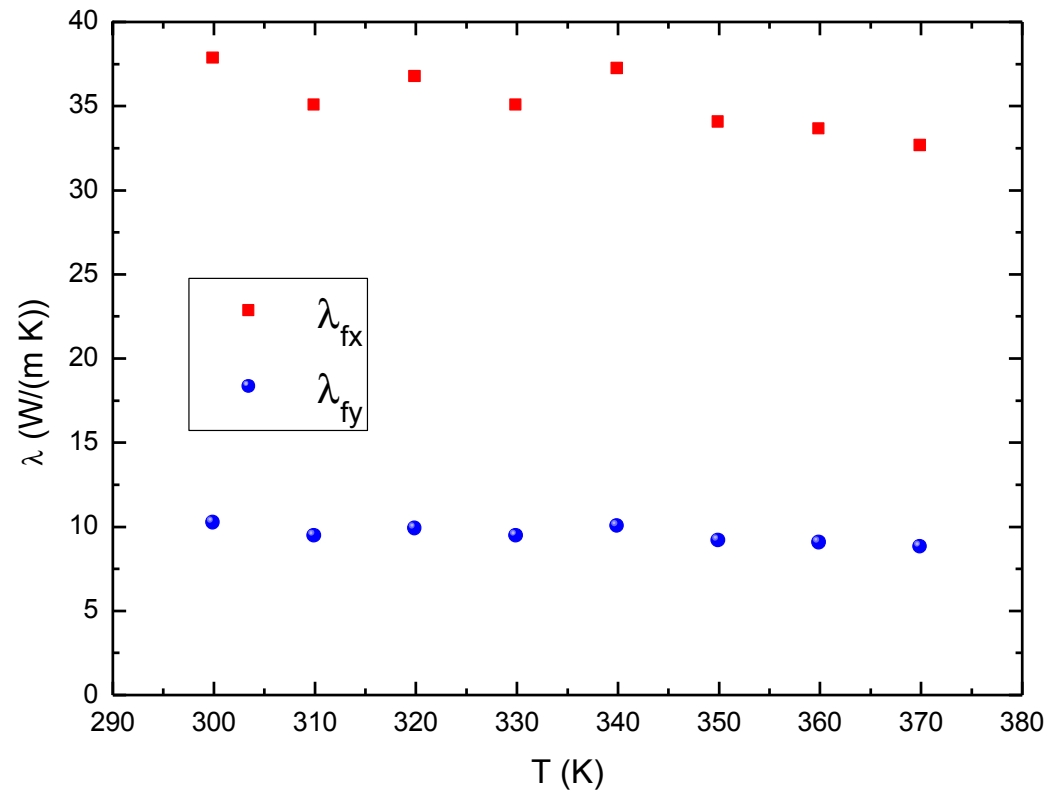
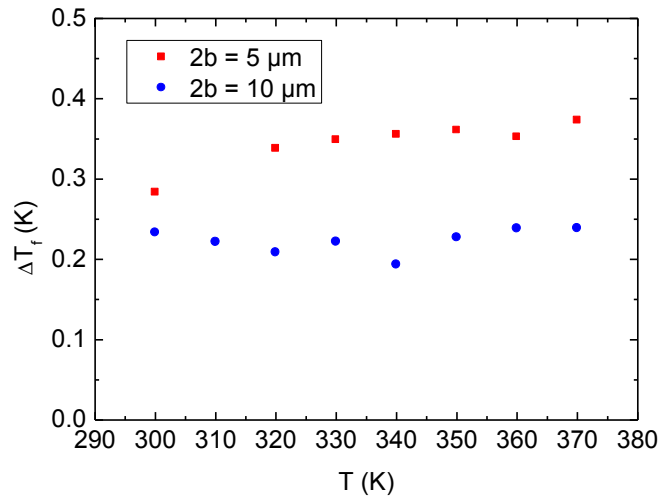
# Thermal conductivity of periodic SLs

- Ge content 1.7 %



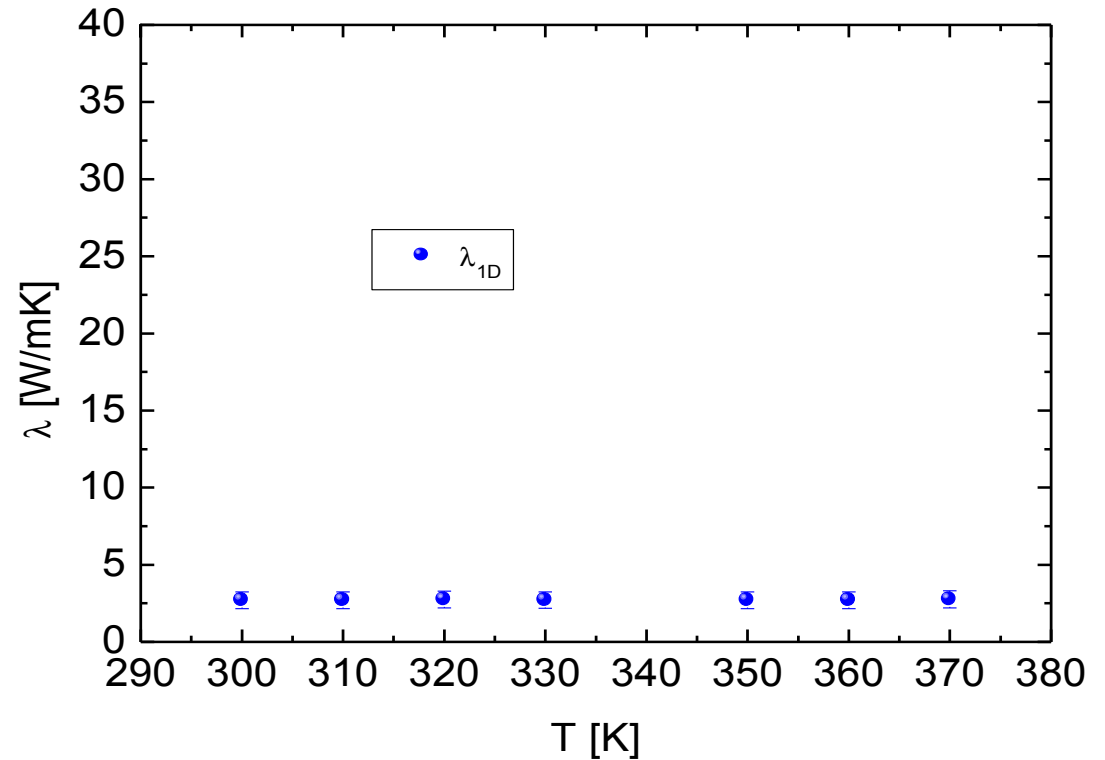
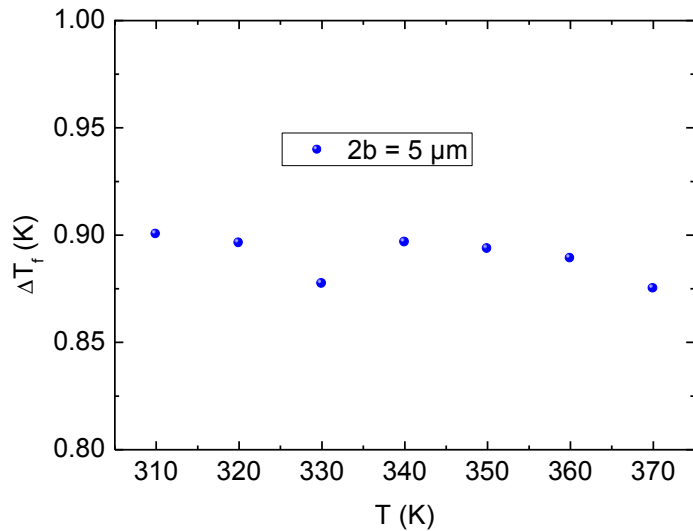
# Thermal conductivity of periodic SLs

- Ge content 3.5 %



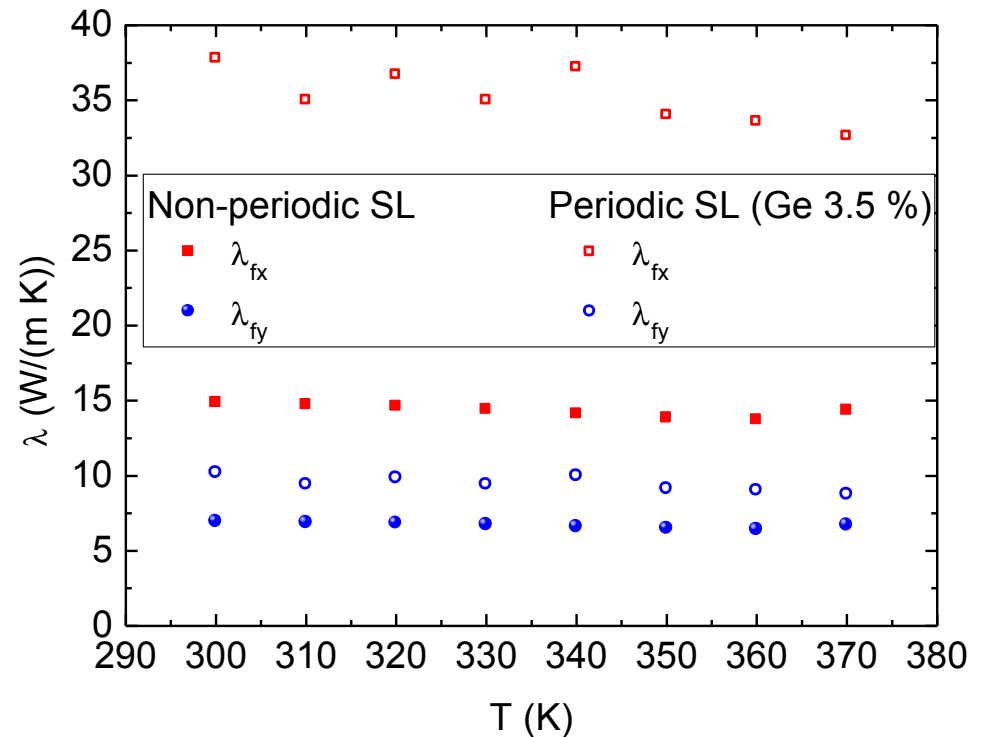
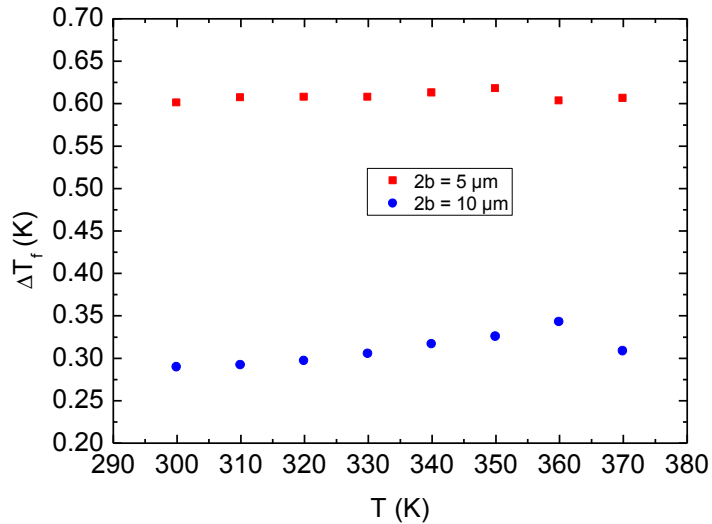
# Thermal conductivity of periodic SLs

Ge content 17%



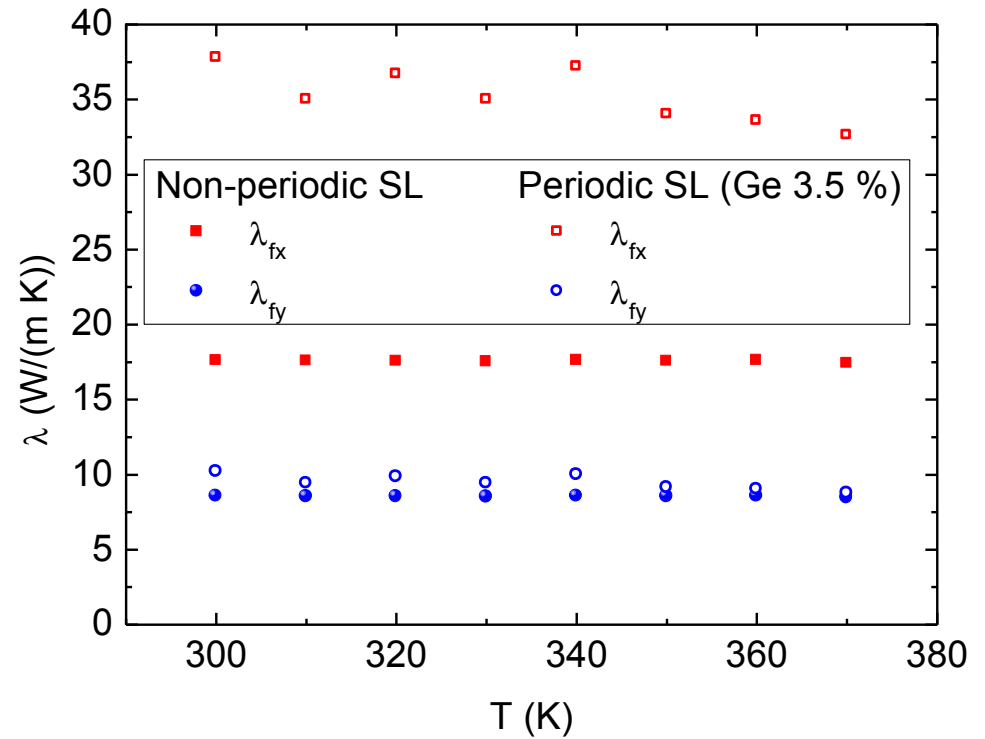
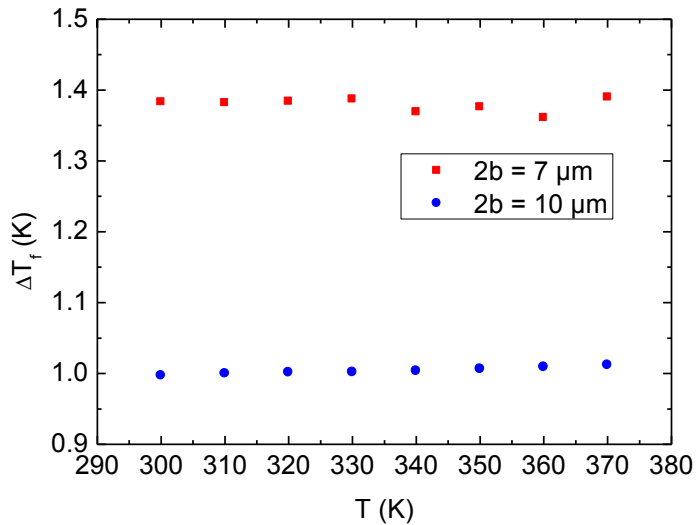
# Thermal conductivity of non-periodic SLs

Ge content 2.9 %

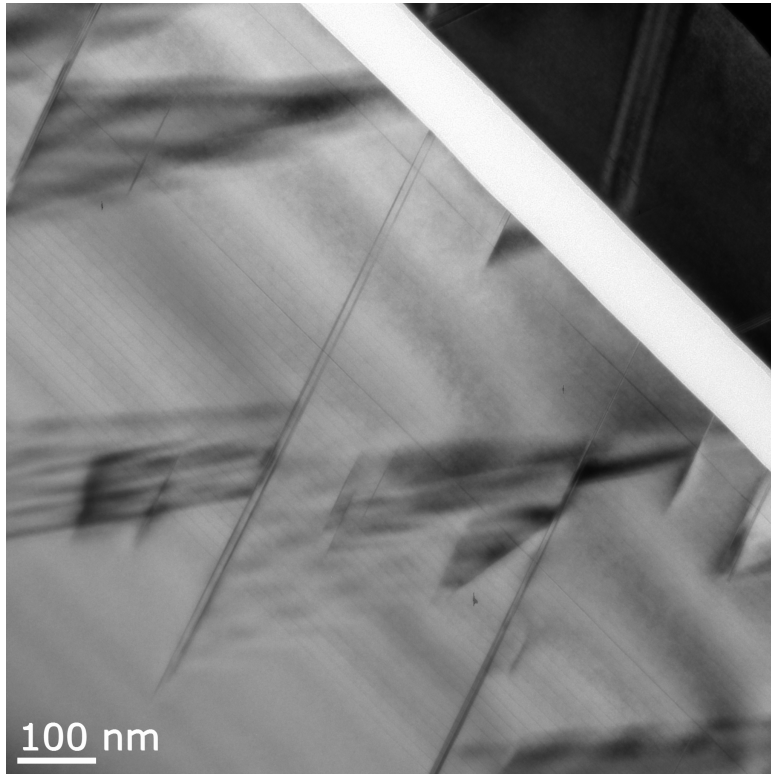


# Thermal conductivity of non-periodic SLs

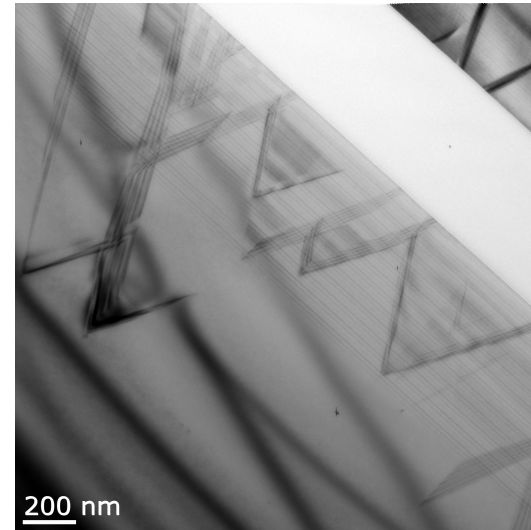
Ge content 3.3 %



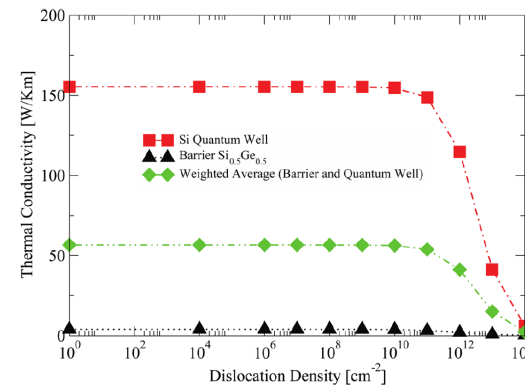
# Defects in MBE grown films



Ge content 3.5 %



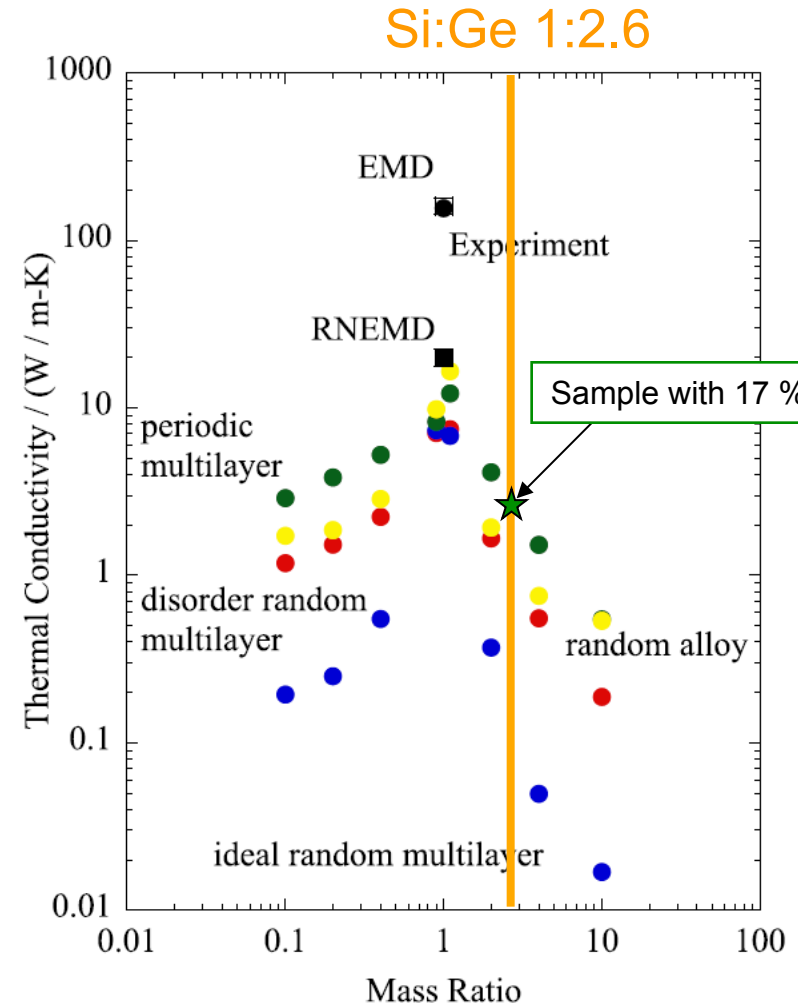
Ge content 2.9 %



J. R. Watling et al., JAP **110**, 114508 (2011)

# Conclusions & Outlook

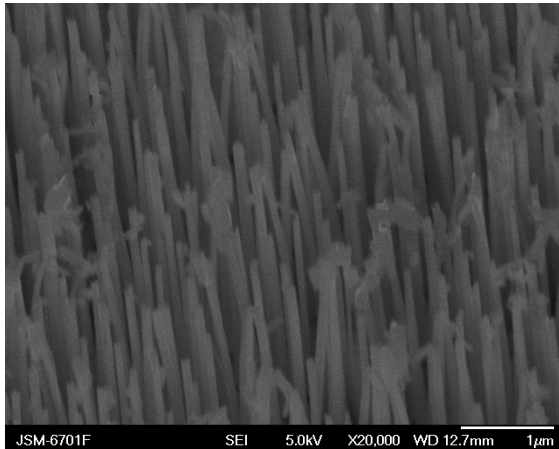
- lowest thermal conductivity for the periodic SL with the highest Ge concentration
- a distinct reduction of the cross-plane thermal conductivity through non-periodicity was not observed
  - theoretical predictions for a material X concentration of 20% with mass ratio Si:X = 1:10
    - Increase Ge concentration
- non-periodicity leads to a 50 % decrease of the in-plane thermal conductivity



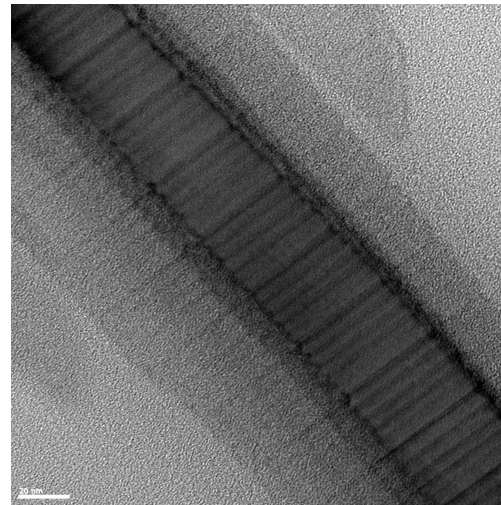
A. Frachioni et al., JAP 112, 014320 (2012)

# Conclusions & Outlook

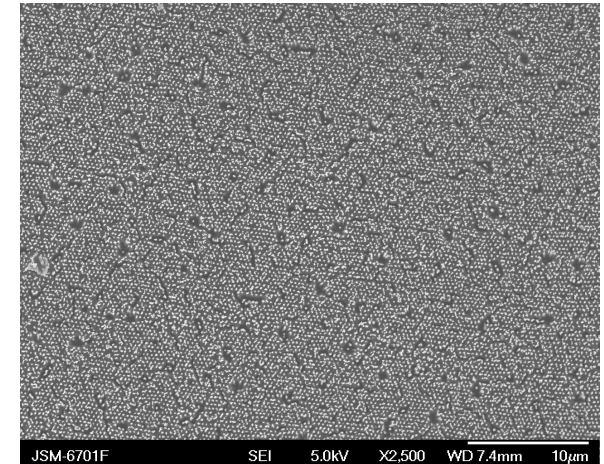
- Thermal conductivity of SLNW Arrays



Array of nanowires



Nanowire  
containing SiGe SL



Embedded nanowire  
array for thermal  
conductivity  
measurement



Thank you!



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